

INFORMATION DISCLOSURE
STATEMENT

BY APPLICANT

Docket: 6047-53173

App: 09/590,795

Applicant: Agarwal et al.

Filed: June 8, 2000

Art Unit: 2811

U.S. PATENT DOCUMENTS

Init.*	Number	Date	Name	Class	Sub	Filed
DV	5,852,307	12/22/98	Aoyama et al.			

FOREIGN PATENT DOCUMENTS

Number	Date	Country	Class	Sub	Filed

OTHER DOCUMENTS

DV	Kaga et al., "Thermal Stability of RuO ₂ Thin Films and Effects of Annealing Ambient on Their Reduction Process," <u>Jpn. J. Appl. Phys.</u> 38:3689-3692 (June 15, 1999).
DV	Hayashide et al., "Fabrication of Storage Capacitance-Enhanced Capacitors with a Rough Electrode," <u>Jpn. J. Appl. Phys.</u> , pp. 869-872 (1990).
DV	Matsui et al., "Thermal Stability of a RuO ₂ Electrode Prepared by DC Reactive Sputtering", <u>Jpn. J. Appl. Phys.</u> 39:256-263 (January 15, 2000).

EXAMINER: *ghuland*

DATE 09/25/02

*Examiner: Initial if considered, whether or not in conformance with MPEP 609; draw line through cite if not in conformance and not considered. Send copy.